

**REMARKS**

Non-elected claims 27-47 were canceled. Claims 10, 18, and 26 were amended to clarify that the fault condition is determined based on the critical dimension variation measurement. If claim 10 were to be written in independent form, it would recite:

10. (For illustrative purposes) A method for determining critical dimension variation, comprising:

providing a wafer having a grating structure comprising a plurality of lines;

illuminating at least a portion of the lines with a light source;

measuring light reflected from the illuminated portion of the lines to generate a reflection profile;

determining a critical dimension variation measurement along a length of the lines based on the reflection profile; and

identifying a fault condition associated with the lines based on the critical dimension variation measurement.

Determining the fault condition is an additional manipulative step rather than a modification of a previously recited step. Applicant respectfully requests the rejection of claims 10, 18, and 26 be withdrawn.

The Examiner is invited to contact the undersigned attorney at (608) 833-0748 with any questions, comments or suggestions relating to the referenced patent application.

Respectfully submitted,



Scott F. Diring  
Reg. No. 35,119

Attorney for Applicant

WILLIAMS, MORGAN & AMERSON  
CUSTOMER NUMBER: 23720

10333 Richmond Dr., Suite 1100  
Houston, Texas 77042  
(713) 934-7000

Date: February 19, 2004